

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

*In re* application of:

**Sang-In Lee, et al.**

Serial No.     **10/525,122**

Filed:           **March 20, 2006**

For:     **Atomic Layer Deposition of High-k  
Metal Silicates**

Examiner:   **Roman, Angel**

Art Unit:     **2812**

Confirmation No.: **2947**

Atty. Docket No.: **067538-5171-US**

**RESPONSE/AMENDMENT**

Mail Stop Amendments  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

In response to the Office Action mailed July 9, 2008, please consider the following proposed amendments to the above-identified application and the remarks herein.

Accompanying this response is a Petition for extension of time with the required fee, to bring the period of response to January 9, 2009. Please amend the application as follows.

**Amendments to the Claims** begin on page 2 of this Amendment.

**Remarks** begin on page 6 of this Amendment.